Manufacturer	Applied Materials
Model	EPI5
Wafer Size Range	
Minimum	150 mm
Maximum	200 mm
Set Size	200 mm
Number of Chambers	3
Process Capabilities	ATM EPI PROCESS
Chamber 1 Description	HTF ATM EPI
Chamber 2 Description	HTF ATM EPI
Chamber 3 Description	HTF ATM EPI
Controller Type	Microprocessor Controller Type
Software Revision Level	B6.30
Temperature Control	Dual Pyrometer
Power Requirements	480 V 300.0 A 50 Hz 3 Phase
Year of Manufacture	1996
Condition	Good

Software Ver: B6.30

CB1 Amps: 300A

SBC Type: V452

Flow Point Model: Nano Valve

Gas Panel Type: Configurable

Wafer Size: 200mm (with conversion kit 150mm is possible)

M-Monitor: CRT

3 Chambers ATM EPI

With digital Flow-Control of the cooling systems with interlock and passphrase (Simens PLC)

HDD was upgraded to RAID System